

ABSTRACT**A Method of Exposing Photo-Resist on an Optical Substrate**

A process for exposing a photo-resist (12) on an optical substrate (1) includes
5 applying a photo-resist (12) to a first surface (13) of the optical substrate (1) and
applying a coating (19) to a second surface (16) of the optical substrate(1). The
second surface (16) is opposite the first surface (13) and the coating (19) has a
refractive index less than the refractive index of the optical substrate (1) and a
refractive index greater than the refractive index of the atmosphere surrounding
10 the optical substrate (1). The photo-resist (13) is then exposed to optical
radiation (4).

Figure 2